



Docket No.: M4065.0237/P237

(PATENT)

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Mark Fischer et al.

Application No.: 10/768,081

Filed: February 2, 2004 Art Unit: 2815

For: DOUBLE BLANKET ION IMPLANT

METHOD AND STRUCTURE

Examiner: E.J. Wojciechowicz

Confirmation No.: 8284

## RESPONSE TO RESTRICTION REQUIREMENT

MS Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

The Restriction Requirement mailed January 25, 2005 (Paper No. 0120), required restriction between:

Group I. Claims 56-70, drawn to a semiconductor device; and

Group II. Claims 40-55 and 71-75, drawn to a method of making a semiconductor device.

In response, Applicant hereby elects Group I, claims 56-70 for continued examination, without traverse.

Application No.: 10/768,081 Docket No.: M4065.0237/P237

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Respectfully submitted,

Thomas J. D'Amico

Registration No.:28,371

Christopher S. Chow

Registration No.: 46,493

DICKSTEIN SHAPIRO MORIN &

OSHINSKY LLP

2101 L Street NW

Washington, DC 20037-1526

(202) 785-9700

Attorneys for Applicant